ATTY, DOCKET NO. U.S. DEPARTMENT OF COMMERCE Form PTO-1449, SERIAL NO. PATENT AND TRADEMARK OFFICE MI22-2380 LIST OF ART CITED BY APPLICANT APPLICANT: Jon P. Daley (Use several sheets if necessary) **FILING DATE GROUP** Filed Herewith Linknown 2822 **U.S. PATENT DOCUMENTS** Filing Date
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Sheet 2 of 5 ATTY. DOCKET NO. Form PTO-1449 U.S. DEPARTMENT OF COMMERCE SERIAL NO. MI22-2380 PATENT AND TRADEMARK OFFICE 10/655,997 LIST OF ART CITED BY APPLICANT (Use several sheets if necessary) APPLICANT: Jon P. Daley **FILING DATE** GROUP September 5, 2003 2812 2822 **U.S. PATENT DOCUMENTS** 'Examiner's Document Date Name Subclass Filing Date Number initials # Appropriate 5,670,298 09/97 Hur AB 6,037,239 03/00 **Jennings** AC 6,096,621 08/00 **Jennings** AD 6,130,140 10/00 Gonzalez AE 6,133,105 10/00 Chen et al. 6,133,116 10/00 Kim et al. 6,177,235 B1 01/01 Francou et al. AH 6,277,709 B1 08/01 Wang et al. AJ 6,277,728 B1 08/01 Ahn et al. FOREIGN PATENT DOCUMENTS Subclass Document Date Country Class Translation Number Yes No AJ AK AL OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) ABSTRACT: How to Eliminate Voiding in Porous-Low-k Dielectrics and The Mechanism of Void Formation; Lin et al.; 4 pages COB Stack DRAM Cell Technology beyond 100 nm Technology Node; Yongjik Park & Kinam Kim; pp. 349.1 -Rubin et al., Shallow-Junction Diode Formation by implantation of Arsenic and Boron Through Titanium-Silicide Films and ..., 17 IEEE Transactions on Electron Devices, No. 1, pp. 183-190 (January 1990). DATE CONSIDERED

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